

ART UNIT: 1794

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT:

Kurt, R.

Attn. Doc. No.: NL 021426 US1

SERIAL NO.:

10/539, 362

EXAMINER: Mulvaney, E. E.

FILED:

June 15, 2005

ART UNIT:

1794

CONFIRMATION No.: 7350

FOR: USE OF bI-LAYER PHOTOLITHOGRAPHIC RESISTS AS NEW
MATERIAL FOR OPTICAL STORAGE

Mail Stop AF Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

AMENDMENT AFTER FINAL OFFICE ACTION

Dear Sir:

In response to the Final Office Action dated May 7, 2009, the Applicant hereby submits this paper within two (2) months (until **July 7, 2009**) of the mailing date of the Office Action, and requests amendment of the above-identified application as follows wherein:

Amendments made to the Claims begin on page 2, and Remarks begin on page 9.

As this paper is being filed within two (2) months of the mailing date of the instant Office Action, applicant respectfully requests that the entry of this paper into the record be expedited to allow the Examiner sufficient time to review the arguments presented herein within the statutory time period.